

## THERMAL PROCESSING FACILITY II



**MODEL:** SEMI CAN EQUIPMENT

**INSTALLATION PLACE:** Cleanroom of “Nanotechnology and Microsystems Laboratory”, Department of Microelectronics

**DESCRIPTION:** 2 horizontal atmospheric furnaces each one composed of a diffusion quartz tube surrounded by 3 resistance-heating coils in which wafers are loaded on a quartz carrier. Digital Process Controller is designed for highly accurate diffusion parameters and interfaces directly with Digital Temperature Controller for complete automation of the process.

### SPECIFICATIONS

1. Tube material: quartz HSQ300, tube length: 1250mm, tube diameter: 141mm.
2. Sample size: from small samples up to 100mm diameter wafers.
3. Sample loading: Manual
4. Gasses: O<sub>2</sub>, N<sub>2</sub> purity: 99,999%, forming gas (H<sub>2</sub>/N<sub>2</sub> mixture)
5. Temperature Range: 300-1100°C

### APPLICATIONS

1. Annealing of metals
2. Annealing of Silicides
3. Annealing of High-k dielectrics

### CERTIFICATION/ACCREDITATION

The facility is not certified or accredited.

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